

P2004,0327

Summary

5 Process for structuring at least one layer as well as electrical
component with structures from the layer

10 The invention states a process to generate at least one structured
layer (10A), wherein a mask structure (20) with a first (20A) and
second structure (20B) is generated on a layer (10) which is present on
a substrate (5). Through this mask structure (20), the first layer
(20A) is transferred onto the layer (10) using isotropic structuring
processes, and the second structure (20B) is transferred onto the layer
15 (10) using anisotropic structuring processes. The process as per the
invention permits the generation of two structures (20A, 20B) in at
least a single layer while using a single mask structure.

20 Significant figure: Figure 1

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